

Gas-phase Electron Diffraction Structure of Tetrameric Prosiloxane, $(\text{H}_2\text{SiO})_4$

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Summary The molecular structure of $(\text{H}_2\text{SiO})_4$ in the vapour phase has been established by electron diffraction.

1.634 Å and angle Si-O-Si 144.1° in disiloxane).⁵ The features in $P(r)/r$ above 3.4 Å can be accounted for by a

THE volatile material of composition $(\text{H}_2\text{SiO})_n$ first obtained by Stock *et al.*^{1,2} was further investigated by Campbell-Ferguson,³ who concluded from the molecular weight and mass spectrum that the predominant oligomer has $n=4$. Examination of the vapour by electron diffraction confirms this conclusion and provides the molecular structure of this tetramer.

Samples of the compound were prepared by the reaction of SiH_2I_2 vapour with copper(I) oxide or hydrated lead(II) oxide, and purified by fractional condensation *in vacuo*; their i.r. and mass spectra agreed with those reported.³ Electron diffraction data were collected photographically at U.M.I.S.T. and processed using our usual techniques.⁴

The radial distribution curve $P(r)/r$ (Figure 1) shows strong peaks at 1.63, 2.70, and 3.13 Å (1 Å = 10^{-10}m). These can be identified with Si-O (bonded), O...O and Si...Si (each across one angle), giving values of 149° for the Si-O-Si angle and 112° for the O-Si-O angle (*cf.* Si-O

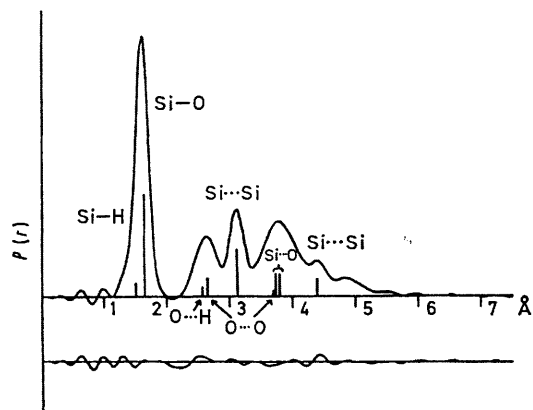


FIGURE 1

puckered cyclic tetramer of S_4 ($\bar{4}$) molecular symmetry, although other cyclic tetramer structures of lower symmetry cannot definitely be excluded. Preliminary least-squares refinements with the S_4 model (assuming further all Si-O bonds equal, all Si-H bonds equal and all H-Si-O angles equal) gave the molecular parameters shown with estimated standard deviations in parentheses in Figure 2.

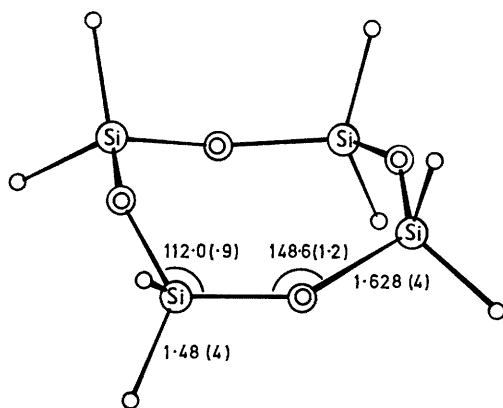


FIGURE 2

The structure can be generated by the symmetry operations of S_4 on the co-ordinates (in Å): O (1.86, 0, 0.31), Si (1.59, 1.51, -0.25), H (2.15, 1.61, -1.61), and H (2.25, 2.47, 0.65). The contributions of the more important non-bonded interatomic distances are indicated in Figure 1: in additions to those given above, these are O...O 3.71, Si...Si 4.38, Si...O 3.72 and 3.80 Å. All features above 4.5 Å are due to Si...H, O...H and H...H atom pairs.

The difference radial distribution curve in Figure 1 provides no evidence for the presence of trimer, pentamer, or other oligomers. For a cyclic trimer, the mean of the Si-O-Si and O-Si-O angles cannot exceed 120°; with reasonable molecular parameters a prominent Si...O peak is expected at about 3.2-3.3 Å, with no strong non-bonded peaks at longer distances. Any pentameric structure with the expected large Si-O-Si angles would possess longer Si...O and Si...Si distances than those of Figure 1: a C_{5v} pentamer with the Si-O distance and angles of Fig. 2 would have O...O 4.37, Si...Si 5.06, Si...O 4.04 and 4.98 Å. The parameters found for $(H_2SiO)_4$ are similar to those reported⁶ for crystalline $(Me_2SiO)_4$ (mean SiO 1.65 Å, mean Si-O-Si 142.5°, and mean O-Si-O 109°).

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